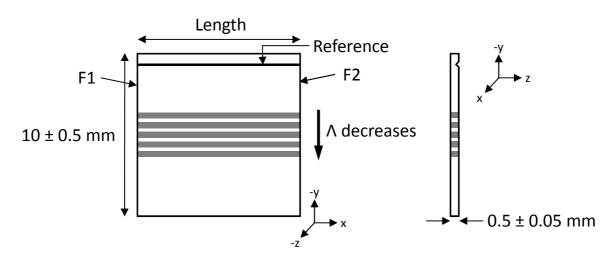
Device Specification MSFG612-0.5-xx



[Image for reference only. Not to scale.]

Description MgO doped PPLN SFG crystal for 1550nm and 1000-1025nm generating 608-617nm

Thickness(z) 0.5mm±0.05mm

Width(y) 10mm±0.5mm

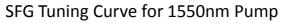
Length(x) 40mm±0.5mm, 20mm±0.5mm, 10mm±0.2mm, 5mm±0.1mm, 3mm±0.1mm, 1mm±0.1mm

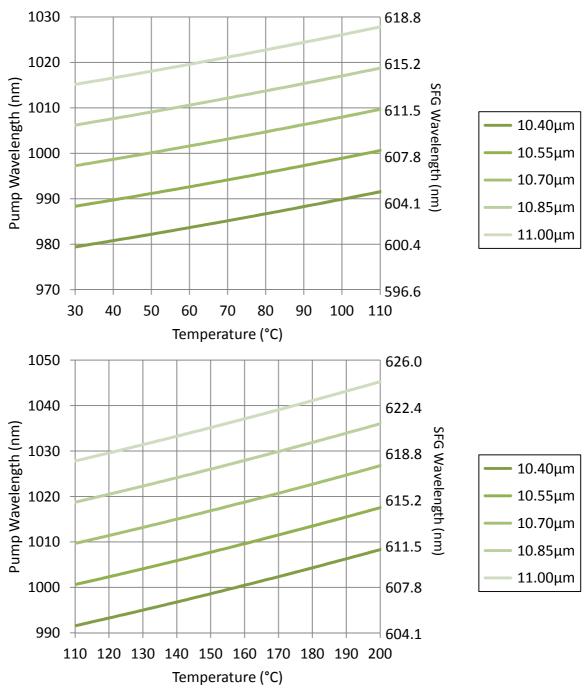
Periods(Λ) 10.40, 10.55, 10.70, 10.85, 11.00μm

NOTES:

- The SFG device material is Magnesium doped Lithium Niobate with five periodically poled gratings. Each grating is 0.5mm wide with individual periods as listed above. A saw-cut reference mark is provided on the +z face of the crystal to determine the largest grating period (see above diagram). Each poled grating is separated by 0.2mm wide regions of unpoled material.
- 2 The average mark-to-space ratio of each grating is better than 70:30.
- 3 Each device is etched to make the poled gratings visible. Due to the wet-etch nature of this process the top and bottom surface finish of each device may appear cloudy or uneven.
- 4 Perpendicularity of input/output facets F1 and F2 to gratings is within ±0.15°. Parallelism between end facets F1 and F2 is within ±5 minutes.
- Optical finish of facets F1 and F2 is within 20/10 scratch dig with $\lambda/4@633$ nm. No more than two 100 μ m size chips per end facet.
- 6 Triple-band AR coating to R<1% 1000-1025nm, 1550nm and 608-617nm on both input/output facets.

Device Specification MSFG612-0.5-xx





Please note these are calculated tuning curves only and actual values may vary.

For more information, please contact us at:

Sintec Optronics http://www.sintec.sg sales@sintec.sg